

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hiroki YOSHIKAWA et al.

Application No.: 10/811,924

Confirmation No.: 3156

Filed: March 30, 2004

Art Unit: 1756

For: PHOTOMASK BLANK, PHOTOMASK, AND
METHOD OF MANUFACTURE

Examiner: S. D. Rosasco

SUPPLEMENTAL AMENDMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

In further response to the Office Action dated April 16, 2007, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.